Poly(acrylamide-co-diallyldimethylammonium chloride) solution (P(Aam-co-DADMAC))	Poor
Poly(ethylene glycol), MW 12000	Excellent
Polyvinylpyrrolidone avg mol wt 10,000	Poor
Poly(ethylene glycol), MW 400	Excellent
Poly(ethylene glycol), MW 1000	Excellent
Poly(ethylene glycol), MW 4000	Excellent
Pluronic L64 (EO13-PO30-EO13)	Excellent
Pluronic 17R4 (PO14–EO24–PO14)	Excellent

[0111] As evident from this table that only those formulations comprising additives with polyethylene glycol groups such as polyethylene glycol (Molecular weights 400, 1000, 4000, 12000), copolymers of polyethylene glycol(PEO) and polypropylene glycol (PPO) such as Pluronic L64 and Pluronic 17R4 provide excellent cleaning performance.

Example 5

[0112] TEOS and SiN wafers were polished with a tungsten buff slurry and cleaned on Mirra polisher using IC1000 pad. The concentrate formulations used were summarized in table 7. Formulations were diluted 1 part formulation to 49 parts water to create point of use cleaning formulations. These formulations were used on Ontrak DSS200 cleaner to clean the wafers. Cleaning was performed on Ontrak cleaner using two brush boxes with a cleaning recipe comprising 30 second chemical dispense and 320 seconds DI water rinse in the first brush box and 10 second chemical dispense and 40 seconds DI water rinse in the second brush box station.